CLAIM AMENDMENTS

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1 – 6. (Cancelled).

7. **(Currently Amended)** A pellicle **operable to transmit light at an exposure wavelength, the pellicle** comprising:

a frame; and

an amorphous fluoropolymer thin film including an optical thickness coupled to the frame, the optical thickness ~~**operable to maximize**~~ **being greater than a design thickness by an amount less than or equal to approximately one-quarter of the exposure wavelength such that** transmission of ~~**an**~~ **light at the** exposure wavelength at an angle of incidence greater than zero **is substantially maximized, the design thickness comprising a thickness of the thin film that maximizes transmission of light incident to the thin film at a normal angle at the exposure wavelength**;

the thin film formed to cooperate with a photomask including an opening ~~**and**~~ **to** facilitate projection of an image ~~**including spatial information associated with the opening**~~ from the photomask onto a surface, the **resolution of the projected image defined at least in part by** spatial information **contained within light diffracted by the opening** ~~**operable to increase resolution of the image**~~.

8. **(Cancelled).**

9. **(Currently Amended)** The pellicle of Claim 7, further comprising **the thin film including an associated** ~~**a**~~ peak in transmission for normal incidence light **at a wavelength** ~~**located**~~ between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

10. (Original) The pellicle of Claim 7, further comprising an anti-reflective coating disposed on a top surface and a bottom surface of the thin film.

11. (Original) The pellicle of Claim 10, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

12. **(Currently Amended)** The pellicle of Claim 10, further comprising **the thin film including an associated** ~~a~~ peak in transmission for normal incidence light **at a wavelength** ~~located~~ between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

13. (Original) The pellicle of Claim 10, wherein the anti-reflective coating includes a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

14. (Original) The pellicle of Claim 7, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

15. (Cancelled).

16. (Original) The pellicle of Claim 7, wherein:

the thin film includes a thickness of approximately 855 nanometers; and

the exposure wavelength is between approximately 248 nanometers and approximately 436 nanometers.

17. **(Currently Amended)** A photolithography system for optimizing off-axis transmission of light, comprising:

a photomask including an opening; and

a pellicle comprising:

a frame coupled to the photomask; and

an amorphous fluoropolymer thin film operable to transmit approximately ninety-nine percent (99%) of off-axis light at an exposure wavelength such that an image of the opening projected onto a surface by the photomask includes spatial information contained in the off-axis light, **the resolution of the projected image defined at least in part by spatial information contained within a portion of the off-axis light diffracted by the opening** ~~**the spatial information operable to increase resolution of the image**~~.

18. **(Currently Amended)** The system of Claim 17, further comprising the thin film including an optical thickness greater than a design thickness by less than or equal to approximately one-quarter of the exposure wavelength, the design thickness **comprising a thickness of the thin film that maximizes transmission of light incident to the thin film at a normal angle at the exposure wavelength** ~~**operable to produce a peak in transmission for normal incidence light at the exposure wavelength**~~.

19. **(Currently Amended)** The pellicle of Claim 17, further comprising **the thin film including an associated** ~~**a**~~ peak in transmission for normal incidence light **at a wavelength** ~~**located**~~ between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

20. (Original) The system of Claim 17, further comprising an anti-reflective coating disposed on a top surface and a bottom surface of the thin film, the anti-reflective coating including a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

21. **(Currently Amended)** The pellicle of Claim 20, further comprising **the thin film including an associated** ~~a~~ peak in transmission for normal incidence light **at a wavelength** ~~located~~ between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

22. (Original) The system of Claim 20, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

23. (Original) The system of Claim 17, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

24. (Original) The system of Claim 17, wherein the frame comprises aluminum.

25. (Cancelled).

26. (Previously Presented) A method for performing photolithography, comprising:

forming an amorphous fluoropolymer thin film including an optical thickness, the optical thickness ~~operable to maximize~~ **being greater than a design thickness by an amount less than or equal to approximately one-quarter of an exposure wavelength such that** transmission of ~~at least one~~ **light at the** exposure wavelength at an angle of incidence greater than zero **is substantially maximized, the design thickness comprising a thickness of the thin film that maximizes transmission of light incident to the thin film at a normal angle at the exposure wavelength**;

attaching the thin film to a frame to form a pellicle;

mounting the pellicle on a photomask including an opening;

exposing the pellicle and the photomask to radiant energy having the exposure wavelength**, the radiant energy being incident upon the pellicle at the angle of incidence greater than zero**; and

projecting the radiant energy through the opening in the photomask to form an image on a surface, the thin film operable to facilitate projection of spatial information associated with the opening**, the resolution of the image projected on the surface being defined at least in part by the projected spatial information** ~~and increase resolution of the image~~.

27. (Original) The method of Claim 26, further comprising coating a top surface of the thin film with an anti-reflective material, the anti-reflective material including a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

28. (Original) The method of Claim 27, further comprising coating a bottom surface of the thin film with the anti-reflective material.

29. **(Currently Amended)** The pellicle of Claim 26, further comprising **the thin film including an associated** ~~a~~ peak in transmission for normal incidence light **at a wavelength** ~~located~~ between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

30. (Original) The method of Claim 26, further comprising coating at least one of a top surface and a bottom surface of the thin film with a plurality of adjoining layers of anti-reflective material, each layer including a different refractive index.